

U.S. Department of Commerce, Patent and Trademark Office		Docket No.	Serial No.
(PTO Form 1449 modified)		AMAT/2966.C1/DSM/BCVD/JW	10/684,079
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Bencher, et al.	Confirmation No. Unknown
(Use several sheets if necessary)		Filing Date	Group
Examiner Unknown		October 9, 2003	Unknown

U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
V.Y.	A17	5,789,776	08/04/1998	Lancaster, et al.	257	296	09/18/1996
↑	A18	5,789,316	08/04/1998	Lu	438	638	03/10/1997
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	A23	5,711,987	01/27/1998	Bearinger, et al.	427	7	10/04/1996
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V.Y.	C3 Ogawa, et al., "Novel ARC Optimization Methodology for KrF Excimer Laser Lithography at Low K Factor", Proceedings of the SPIE. Optical/Laser Microlithography Vol. 1674, 1992, pages 362-375.
N.Y.	C4 Dijkstra, et al., "Optimization of Anti-Reflection Layers for Deep UV Lithography", Proceedings of SPIE Optical Laser Microlithography, Bellingham, SPIE, Vol. 1927, pages 275-286.
N.Y.	C5 PCT International Search Report for PCT/US99/22424, Dated March 9, 2000.
V.Y.	C6 PCT International Search Report for PCT/US99/22317, Dated March 21, 2000.

Examiner

Date Considered 04/29/05

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		Applicant Benchner, et al.	Confirmation No. Unknown
Examiner Unknown		Filing Date October 9, 2003	Group Unknown



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*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
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Date Considered

04/29/05

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